CCD Image Anomalies Caused by Unpainted Filter Edges, CCD Photo-Response Non-Uniformity and Mitigated CCD Residual Bulk Image Trap Leakage

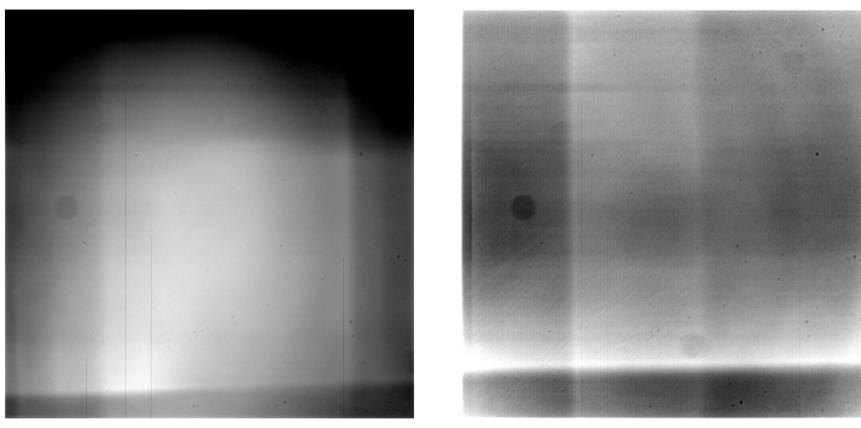
> R. D. Crisp Feb 12, 2011 <u>rdcrisp@earthlink.net</u>

www.narrowbandimaging.com

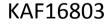
# Key Points

- Flats taken using CCDs and square filters with unpainted edges exhibit anomalies
  - Straight line 'blocky-shadows' and straight lines demarcating lighter versus darker regions appear in some flats
- Filter Edge Artifacts were eliminated by blackening edges of filters using a Testor's brand Flat Black Enamel Pen
- Other artifacts are due to CCD Photoresponse nonuniformity and Mitigated Residual Bulk Image (RBI) Trap Leakage
- Proper calibration eliminates all artifacts except for filter edge artifacts, which are eliminated by edge painting

# Examples (non-edge blackened square filters)

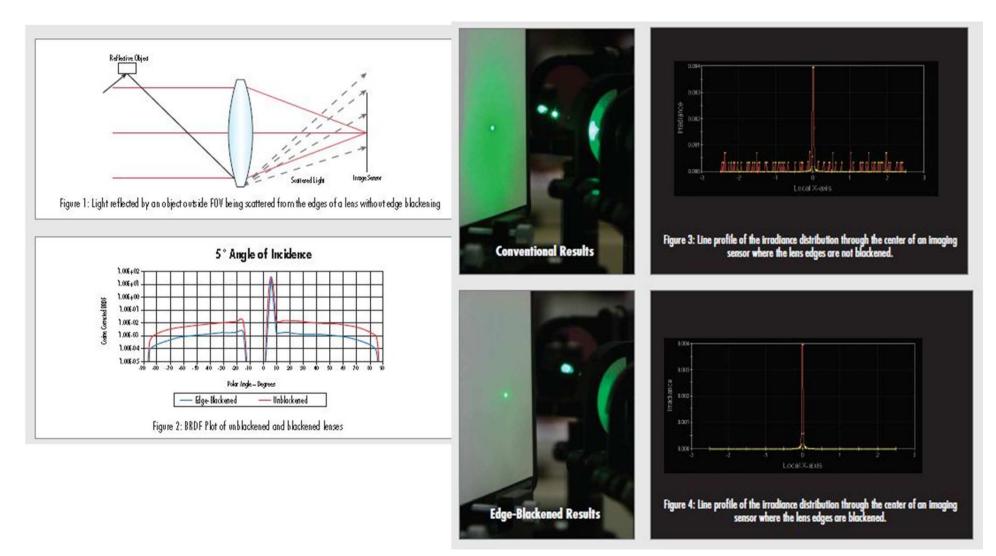








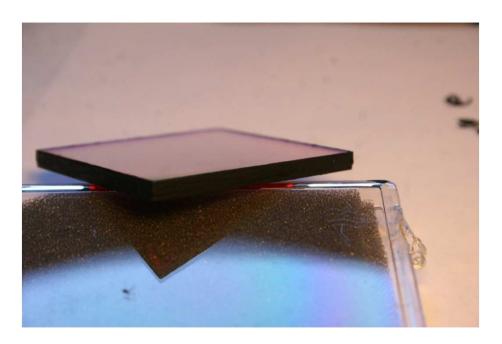
## Edge Blackening



Source: Edmund Industrial Optics "Why Use Edge-Blackened Optics?"

#### Blackening the Edges





2549C Enamel Paint Marker Flat Black by Testor Corp.

Be the first to review this item

Source: Adrien Richardson

Price: \$3.70

#### In Stock.

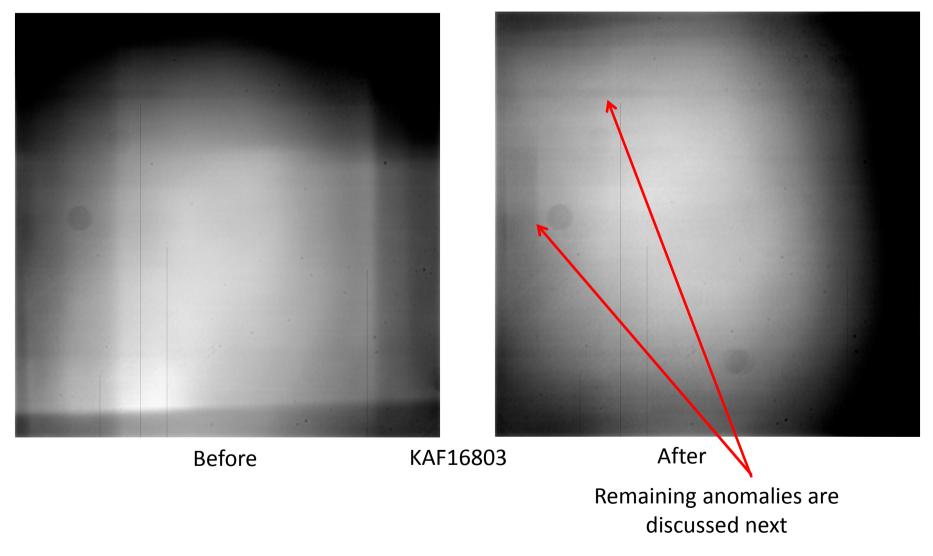
Ships from and sold by Best Service Stores.

Only 2 left in stock--order soon.

4 new from \$3.70

Source: Amazon.com

### Before/After Edge Blackening

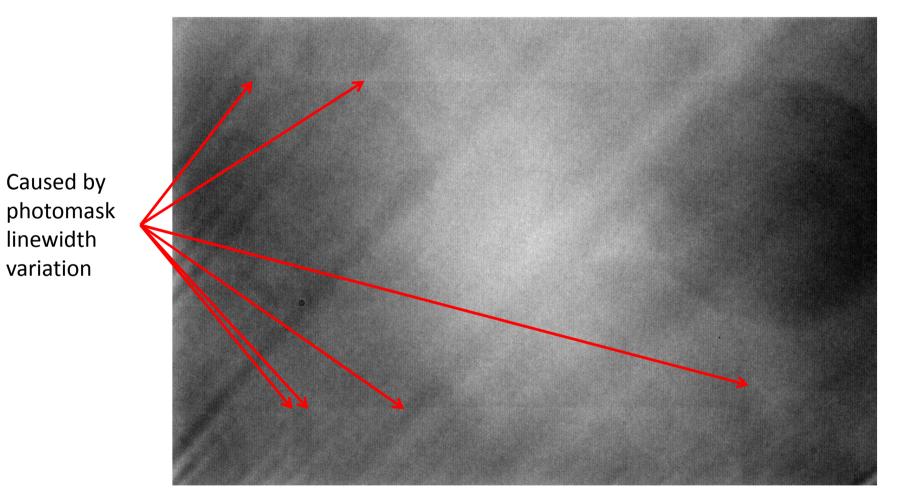


Source: Adrien Richardson

### **PRNU** Anomalies

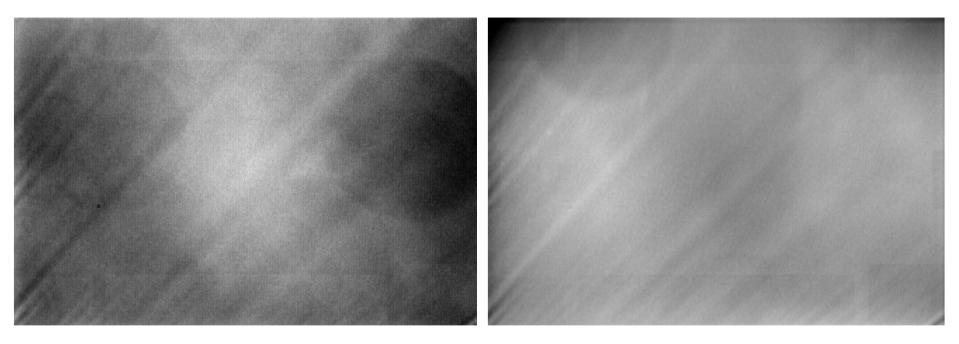
- Fabrication processes for CCDs use photolithography for making required structures on the silicon wafer
- The wafers are coated with a photosensitive thin film, exposed via a photomask and then processed creating the CCD's circuitry on the silicon wafer
- The photomasks are made using an electron-beam with a finite spot size.
- Minor variations in line widths on the photomask arise from the finite spot size and the need for the beam to "snap to grid" to cut the design features
  - The features to be etched may not lie perfectly on Ebeam boundaries
  - This causes dimensional variation in the resulting etched features on the photomask
- These result in linewidth variations on the CCD that cause some pixels to be slightly larger than others
- This leads to visible artifacts in images arising from Photo Response Non Uniformity (PRNU), an important CCD performance specification
- These artifacts are completely removed by proper flat fielding

### Examples of Photomask-Induced PRNU Artifacts



KAF3200ME Halpha flat using 50mm ROUND filter

# Multiple PRNU Artifacts (all are removable by flat-fielding)

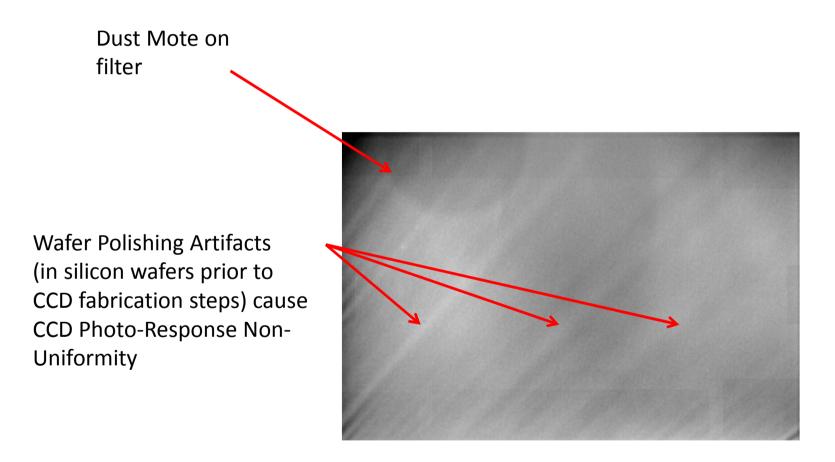


KAF3200ME Halpha flat using 50mm ROUND filter KAF3200ME [OIII] flat using 50mm ROUND filter

Note the photomask-induced artifacts are identical (the blocky shapes with straight edges oriented horiz and vert) NOT CAUSED BY FILTER EDGES

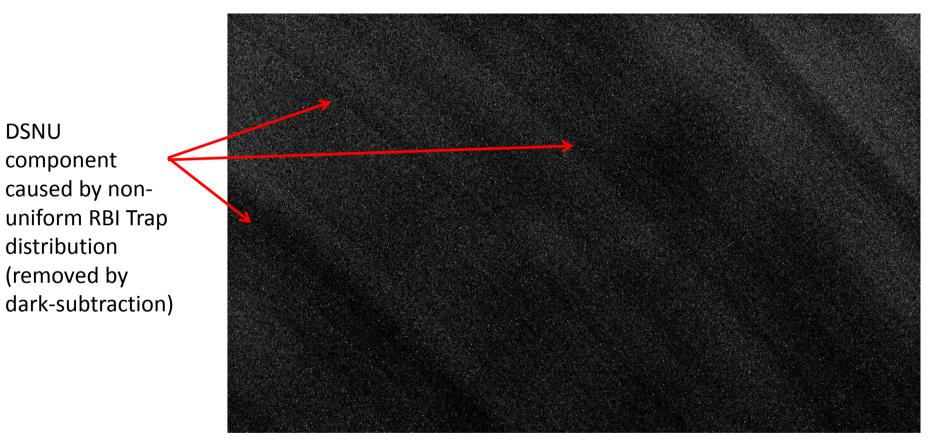
Source: Crisp

# Non Photomask Artifacts (all are removable by flat-fielding)



KAF3200ME [OIII] flat using 50mm ROUND filter

# Dark Signal Non-Uniformity (DSNU) For RBI Mitigated Camera

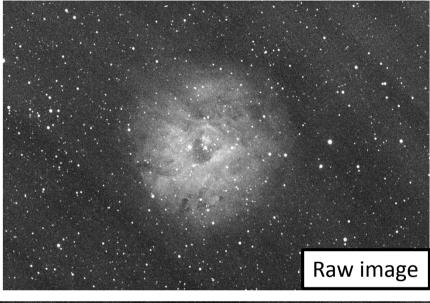


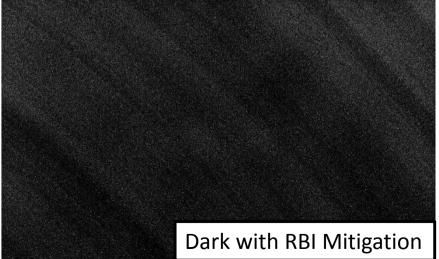
KAF3200ME Dark

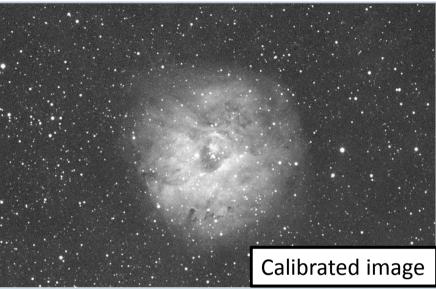
Classic DSNU "Dark Spikes" (salt and pepper features) (removed by dark-subtraction)

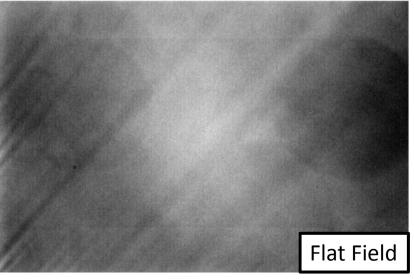
Source: Crisp

# **Before/After Calibration**









Source: Crisp